

ABSTRACT OF THE DISCLOSURE

A photo mask includes a transmission region, a half-tone region, and a light-shielding region, and is formed in a one-time writing method. An outer periphery of each of a plurality of transmission regions is surrounded
5 by the half-tone region. In a densest pattern region having a plurality of transmission regions arranged at a pitch of at most $0.32\text{ }\mu\text{m}$ which is smallest in the photo mask, the half-tone region surrounding an outer periphery of each of a pair of transmission regions is configured such that the light-shielding film is positioned between a pair of transmission regions
10 adjacent to each other. Therefore, for a tri-tone mask, a photo mask, free from a forbidden region for all pitches, a method of manufacturing a electronic device, and a method of manufacturing a photo mask result.